## IN THE SPECIFICATION:

Page 13, line 22 to Page 14, line 16, please amend as follows:

## (Thirty-ninth embodiment)

There is provided a method of fabricating a liquid crystal display device comprising: fabricating a first bottom-gate TFT array substrate including forming at least a gate wiring line metal film, a gate insulating film, and a semiconductor film on a surface of an insulating substrate; by photolithography, sequentially etching the semiconductor film, the gate insulating film, and the gate wiring line metal film, using a first pattern; oxidizing side surfaces of portions of a gate wiring line metal film pattern to be formed into gate wiring lines and gate electrodes; forming a contact metal film and a metal electrode film; and by photolithography, etching part of the metal electrode film, the contact metal film, and the semiconductor film, using a second pattern; forming an alignment film on the first substrate; forming an alignment film on a surface of a counter electrode side of a second color filter substrate having a counter transparent electrode formed thereon; adhering and fixing the first and second substrates and the color filter substrate at the periphery thereof such that the substrates are

arranged with the two alignment films facing inside and with a predetermined gap maintained between the substrates; and injecting a specified liquid crystal between the first and second substrates.

Page 24, line 8 to page 25, line 1, please amend as follows:

(Seventy-fifth embodiment)

There is provided a method of fabricating a liquid crystal display device comprising: fabricating a first bottom-gate TFT array substrate including forming at least a gate wiring line metal film, a gate insulating film, and a semiconductor film on a surface of an insulating substrate; by photolithography, sequentially etching the semiconductor film, the gate insulating film, and the gate wiring line metal film, using a first pattern; oxidizing side surfaces of portions of a gate wiring line metal film pattern to be formed into gate wiring lines, gate electrodes, and first comb-shaped electrodes; forming a contact metal film layer and a metal electrode film; by photolithography, etching part of the metal electrode film, the contact metal film layer, and the semiconductor film, using a second pattern;

forming an alignment film on the first substrate; forming an alignment film on a surface of a counter electrode side of a second color filter substrate; adhering and fixing the first and second substrates and the color filter substrate at the periphery thereof such that the substrates are arranged with the two alignment films facing inside and with a predetermined gap maintained between the substrates; and injecting a specified liquid crystal between the first and second substrates.

## Page 54, lines 4-15, please amend as follows:

First, there were provided a TFT array substrate for the IPS mode device, similar to that of Example 2-5, fabricated using two masks, more specifically, a first TFT array substrate including a first comb-shaped electrode group and a second comb-shaped electrode group arranged in a matrix and a transistor group that drives the <u>first comb-shaped electrode group; and a second comb-shaped electrode group; and a color filter substrate including a second color filter substrate including a second color filter substrate including a color filter group placed opposite to the first and second electrode groups. Over each of the substrates, by a conventional method, a polyimide resin was applied and cured, and the resulting films were</u>

subjected to rubbing, thus producing liquid crystal alignment films.

Page 58, line 15 to Page 59, line 1, please amend as follows:

## Example 2-8

The actual fabrication process of a liquid crystal display device using the above-described TFT array substrate is described.

First, there were provided a TFT array substrate for the IPS mode device, similar to that of Example 2-7, fabricated using two masks, more specifically, a first TFT array substrate including a first comb-shaped electrode group and a second comb-shaped electrode group arranged in a matrix and a transistor group that drives the second-first comb-shaped electrode group; and a second color filter substrate including a color filter group placed opposite to the first and second electrode groups. Over each of the substrates, by a conventional method, a polyimide resin was applied and cured, and the resulting films were subjected to rubbing, thus producing liquid crystal alignment films.